

L Number	Hit#	Search Text	DB	Time stamp
6	892	SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAII TOSHIKI AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/27 13:01
7	101	(SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAII AOAI-T AOAI-TOSHIKI AOAII-TOSHIKAI-C-O-FUJI-PHOTO-F AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F) and lactone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/27 13:01
8	18	(US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280898-\$ or US-6548220-\$ or US-5695906-\$ or US-6461788-\$).did. or (US-20020009666-\$ or US-200200132181-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$ or US-20010044070-\$ or US-20030059715-\$).did. or (JP-2001240625-\$ or JP-2001188346-\$ or JP-2001142213-\$).did.	USPAT; US-PGPUB; EPO; JPO;	2004/05/27 13:02
9	99	((SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAII AOAI-T AOAI-TOSHIKAI AOAII-TOSHIKAI-C-O-FUJI-PHOTO-F AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F) and lactone ) not ((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280898-\$ or US-6548220-\$ or US-5695906-\$ or US-6461788-\$).did. or (US-20020009666-\$ or US-200200132181-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$ or US-20010044070-\$ or US-20030059715-\$).did. or (JP-2001240625-\$ or JP-2001188346-\$ or JP-2001142213-\$).did.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/27 13:13
10	47	((alicyclic adamantanane cyclohexane norbornane) adj lactone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/27 13:14
11	8	((SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAII AOAI-T AOAI-TOSHIKAI AOAII-TOSHIKAI-C-O-FUJI-PHOTO-F AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F) and ((alicyclic adamantanane cyclohexane norbornane) adj lactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/27 13:13
12	39	((alicyclic adamantanane cyclohexane norbornane) adj lactone) not ((SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAII AOAI-T AOAI-TOSHIKAI AOAII-TOSHIKAI-C-O-FUJI-PHOTO-F AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F) and ((alicyclic adamantanane cyclohexane norbornane) adj lactone))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/27 13:21
13	2	("6306554").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/27 13:21

	1863077	resin resist photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 13:55
-	8221	((resin resist photoresist) and (acid near generat\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:17
-	1522	"3" and (positive near composition)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:24
-	203	((resin resist photoresist) and (acid near generat\$4)) and (positive near composition)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:24
-	3892	((resin resist photoresist) and (acid near generat\$4)) and (positive )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:43
-	0	("us-20010039080-A1.did.*).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:32
-	2	(*20010039080").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 12:32
-	0	20010039080.URPN.	USPAT	2002/10/10 12:43
-	801	((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 14:19
-	288	((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:45
-	721	SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOA-T AOA-TOSHIKI AOAI-TOSHIKAI-C-O-FUGI-PHOTO-F AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 14:57
-	30	(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOA AOA-T AOAI-TOSHIKAI AOA-TOSHIKAI-C-O-FUGI-PHOTO-F AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 18:35
-	258	(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not (((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOA AOA-T AOAI-TOSHIKAI AOA-TOSHIKAI-C-O-FUGI-PHOTO-F AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/10 16:06
-	79	(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not (((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOA AOA-T AOAI-TOSHIKAI AOA-TOSHIKAI-C-O-FUGI-PHOTO-F AOAI-TOSHIKAI-C-O-FUJI-PHOTO-F)) and (lactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 14:57

	289	(({{resin resist photoresist}) and (acid near generat\$4)}) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 15:00
	723	SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOA-T AOA-TOSHIKI AOAI-TOSHIKI-C-O-FUGI-PHOTO-F AOAI-TOSHIKI-C-O-FUJI-PHOTO-F	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 15:01
	259	(({{resin resist photoresist}) and (acid near generat\$4)}) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4) ) not (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAIAOAI-T AOAI-TOSHIKI AOA-TOSHIKI-C-O-FUGI-PHOTO-F AOAI-TOSHIKI-C-O-FUJI-PHOTO-F)) and (lactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 18:38
	79	(({{resin resist photoresist}) and (acid near generat\$4)}) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not (({{resin resist photoresist}) and (acid near generat\$4)}) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAIAOAI-T AOAI-TOSHIKI AOA-TOSHIKI-C-O-FUGI-PHOTO-F AOAI-TOSHIKI-C-O-FUJI-PHOTO-F)) and (lactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 18:38
	180	(({{resin resist photoresist}) and (acid near generat\$4)}) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4) ) not (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAIAOAI-T AOAI-TOSHIKI AOA-TOSHIKI-C-O-FUGI-PHOTO-F AOAI-TOSHIKI-C-O-FUJI-PHOTO-F ) ) not (({{resin resist photoresist}) and (acid near generat\$4)}) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4) ) not (({{resin resist photoresist}) and (acid near generat\$4)}) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAIAOAI-T AOAI-TOSHIKI AOA-TOSHIKI-C-O-FUGI-PHOTO-F AOAI-TOSHIKI-C-O-FUJI-PHOTO-F)) and (lactone) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 16:11
	2	US-20010039080-\$ .did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/15 19:07
	549	(resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/16 11:41
	96	((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and( (norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/16 11:44
	71	((resist photoresist) and (norborn\$5) and (\$5acid near generat\$3)) and( (norborn\$5) same (conventional enhanc\$5 improv\$5 benef\$3))) and positive	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 14:20
	325	norbornene same (acrylate methacrylate) same (maleic adj anhydride)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/16 11:54
	7	"6284429"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/10/16 14:53

	18	((((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) ) and (lactone) and ((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or (US-20020009666-\$ or US-20010041303-\$ or US-20020132181-\$ or US-20020058441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010018969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did.) (((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) ) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAII AOAII-T AOAII-TOSHIKAI AOAII-TOSHIKAI-C-O-FUGI-PHOTO-F AOAII-TOSHIKAI-C-O-FUJI-PHOTO-F)).did. ((US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or (US-20020009666-\$ or US-20010041303-\$ or US-20020132181-\$ or US-20020058441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010018969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did. or (JP-2001142213-\$ or JP-2001188346-\$ or JP-2001240625-\$).did.)	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2004/05/26 19:02
	341	(resist photoresist) and (lactone) and ((maleic adj anhydride) (maleimide)) and (norbornene norbornyl)	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2003/10/24 14:41
	17155	(acid photoacid) near generat\$4	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2003/10/24 14:41
	87099	positive near5 (composition working image pattern type)	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2003/10/24 14:44
	4069	((acid photoacid) near generat\$4) and (positive near5 (composition working image pattern type))	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2003/10/24 14:45
	235	((acid photoacid) near generat\$4) and (positive near5 (composition working image pattern type))) and ((resist photoresist) and (lactone) and ((maleic adj anhydride) (maleimide)) and (norbornene norbornyl))	USPAT; US-PPGPUB; EPO; JPO; DERWENT	2003/10/24 14:45

	930	((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 16:59
	0	((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial )) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4) and ((resist photoresist) and (lactone) and ((maleic adj anhydride) (maleimide)) and (norbornene norbornyl)) ((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial )) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:00
	49	((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial )) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:10
	24	((fluorine silicon) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial )) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT	2003/10/24 17:06
	2	(*4822713*).PN.	USPAT; US-POPUB; EPO; JPO; DERWENT	2003/10/24 17:06
	138	(fluorine-type silicon-type) near5 surfactant	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:10
	4	((fluorine-type silicon-type) near5 surfactant) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:11
	13952	((fluorine-type silicon-type) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial )) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT; US-POPUB; EPO; JPO; DERWENT	2003/10/24 17:11
	0	((fluorine-type silicon-type) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial )) and (positive near5 (composition working image pattern type)) and ((acid photoacid) near generat\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:12
	1	((fluorine-type silicon-type) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial )) and (positive near5 (composition working image pattern type))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:12
	18	((fluorine-type silicon-type) near5 surfactant) same (conventional improvement enhance enhancement improve benefit beneficial )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/10/24 17:12
	6	(*6519659*) or (*5478869*) or (*6280898*).PN.	USPAT; US-POPUB; EPO; JPO; DERWENT	2004/05/22 17:44
	0	20010044070.URPN.	USPAT	2004/05/22 19:11
	0	20020009666.URPN.	USPAT	2004/05/22 19:14
	55	(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norbornen\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/05/26 18:47

		186	(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not (((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and (lactone)	USPAT; US-PPGPUB; EPO; JPO; DERVENT	2004/05/26 19:02
		55	(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)	USPAT; US-PPGPUB; EPO; JPO; DERVENT	2004/05/26 19:01
		9	{"4018767"   "4166915"   "4188219"   "5185143"   "5541344"   "5811462"   "5910392"   "6008306"   "6057083").PN.	USPAT	2004/05/26 18:55
		13	6280898.URPN.	USPAT	2004/05/26 18:57
		55	(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F)	USPAT; US-PPGPUB; EPO; JPO; DERVENT	2004/05/26 19:02
		186	(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not (((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and (lactone)	USPAT; US-PPGPUB; EPO; JPO; DERVENT	2004/05/26 19:24

	20	<p>(((((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) ) and (lactone)) and (((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280098-\$).did. or (US-20010041303-\$ or US-20020009666-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did.)</p> <p>(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) ) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F ) )) ) not ((US-6448420-\$ or US-6280098-\$ or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$).did. or (US-20020009666-\$ or US-20010041303-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did. or (JP-2001142213-\$ or JP-2001188346-\$ or JP-2001240625-\$).did.)</p> <p>(US-6251560-\$ or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6248920-\$ or US-6207342-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280098-\$ or US-6548220-\$ or US-5695906-\$ or US-6461788-\$).did. or (US-20020009666-\$ or US-20020132181-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$ or US-20010044070-\$ or US-20030059715-\$).did. or (JP-2001240625-\$ or JP-2001188346-\$ or JP-2001142213-\$).did.</p>	USPAT; US-PGPUB; JPO	2004/05/26 19:02
	38	<p>(US-6251560-\$ or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6248920-\$ or US-6207342-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$ or US-6448420-\$ or US-6280098-\$ or US-6548220-\$ or US-5695906-\$ or US-6461788-\$).did. or (US-20020009666-\$ or US-20020132181-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$ or US-20010044070-\$ or US-20030059715-\$).did. or (JP-2001240625-\$ or JP-2001188346-\$ or JP-2001142213-\$).did.</p>	USPAT; US-PGPUB; JPO	2004/05/26 19:02

	20	(((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) ) and (lactone) and (((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or (US-20010041303-\$ or US-20020009666-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did.) (((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F ) ) ) not (((US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or (US-20020009666-\$ or US-20010041303-\$ or US-20020132181-\$ or US-20020098441-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$).did. or ((JP-2001142213-\$ or JP-2001188346-\$ or JP-2001240625-\$).did.)	USPAT: US-PGPUB; EPO; JPO; DERWENT	2004/05/26 19:05
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	<p>167 (((((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) not ((((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO</p> <p>SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T  AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F  AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) and  (lactone) ) not (((4018767"   "4166915"    "4188219"   "5185143"   "5541344"    "5811462"   "5910392"   "6008306"    "6057083") ,PN, 6280898,URPN, (US-6251560-\$ or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or  US-6448420-\$ or US-6280898-\$ or US-6548220-\$ or US-5695906-\$ or US-6461788-\$).did. or  (US-20020009666-\$ or US-20020132181-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$ or US-20010044070-\$).did. or  (JP-2001240625-\$ or JP-2001188346-\$ or JP-2001142213-\$).did.)  ((((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO</p> <p>SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T  AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F  AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F) )  (((((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) ) and (lactone) ) and  ((US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or  US-6448420-\$ or US-6280898-\$ or US-6548220-\$ or US-5695906-\$ or US-6461788-\$).did. or  (US-20020009666-\$ or US-20020132181-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$ or US-20010044070-\$).did.)  ((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO</p> <p>SATO-KENICHIRO-C-O-FUJI-PHOTO AOAI AOAI-T  AOAI-TOSHIAKI AOAI-TOSHIAKI-C-O-FUGI-PHOTO-F  AOAI-TOSHIAKI-C-O-FUJI-PHOTO-F))) ) not  ((US-6448420-\$ or US-6280898-\$ or US-6403280-\$ or US-6388101-\$ or US-6329125-\$ or US-6303266-\$ or US-6284429-\$ or US-6270941-\$ or US-6251560-\$ or US-6248920-\$ or US-6207342-\$ or US-6200725-\$ or US-6077644-\$ or US-6013416-\$ or US-5968713-\$ or US-5929271-\$ or US-5910392-\$).did. or  ((US-20020009666-\$ or US-20020132181-\$ or US-20020081523-\$ or US-20020061465-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$ or US-20010044070-\$).did.)  ((((resin resist photoresist) and (acid near generat\$4)) and (positive )) and (norborn\$5 alicyclic)) and (alkaline adj develop\$4)) and (SATO-KENICHIRO</p>	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/05/26 19:24
Search History	5/27/2004 10:59:27 AM - US-5910392-\$ did. or US-20020009666-\$ or US-20020058201-\$ or US-20020051936-\$ or US-20020051935-\$ or US-20020048724-\$ or US-20020009668-\$ or US-20020009667-\$ or US-20020004569-\$ or US-20010038969-\$ or US-20010033989-\$ or US-20010018162-\$ or US-20010010890-\$ or US-20010003640-\$ or US-20010044070-\$.		
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